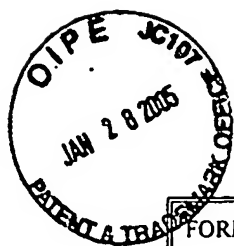


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		APPLICANTS Chung J. Lee and Atul Kumar					
		FILING DATE March 31, 2004		GROUP ART UNIT 2811			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.	
<i>a</i>	3,503,903	3/31/70	Shaw et al.			/	
<i>a</i>	6,086,952	7/11/00	Lang et al.				
<i>a</i>	6,130,171	10/10/00	Gomi				
<i>a</i>	6,265,320	7/24/01	Shi et al.				
<i>a</i>	6,455,443	9/24/02	Eckert et al.				
<i>a</i>	6,495,208	12/17/02	Desu et al.				
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO	
OTHER DOCUMENTS							
<i>a</i>	<i>Parylene Copolymers</i> , Taylor et al., <i>Low Dielectric Constant Materials III</i> , pp. 197-205, 1997.						
<i>a</i>	<i>Finer Copper Wires Make for Faster Integrated Circuits</i> , Preuss, <i>Research News</i> , pp. 1-3, April 5, 1999.						
<i>a</i>	<i>Study of Hydrogen Annealing of Ultrahigh Molecular Weight Polyethylene Irradiated with High-Energy Protons</i> , Wilson et al., <i>Journal of Materials Research</i> , Vol. 14, No. 11, November 1999.						
<i>a</i>	<i>A Novel Oxazole Based Low k Dielectric Addresses Copper Damascene Needs</i> , Schmid et al., <i>Semiconductor Fabtech</i> , 12 th Edition, pp. 231-235, July 2000.						
<i>ch</i>	<i>The Effect of Water Desorption and Organosilane Coupling Agents on the Adhesion of Poly(p-xylylene) Films to a Silicon Wafer Surface</i> , Lightfoot et al., <i>Journal of Materials Science: Materials in Electronics</i> , Vol. 12, pp. 581-586, 2001.						
<i>a</i>	<i>Current Technical Trends: Dual Damascene & Low-k Dielectrics</i> , Healey on behalf of Threshold Systems, pp. 1-6, © 2002.						
EXAMINER <i>[Signature]</i>			DATE CONSIDERED <i>4-7-05</i>				

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FORM PTO-1449		DOCKET NUMBER DSI 301		APPLICATION NUMBER 10/816,205		
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U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
a	3,268,599	08/23/1966	Chow			
a	3,274,267	09/20/1966	Chow			
a	3,280,202	10/18/1966	Gilch			
a	3,288,728	11/29/1966	Gorham			
a	3,332,891	07/25/1967	Chow et al.			
a	3,342,754	09/19/1967	Gorham et al.			
a	3,349,045	10/24/1967	Gilch			
a	3,379,803	04/23/1968	Tittmann et al.			
a	3,503,903	03/31/1970	Shaw et al.			
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
a	EP 0 349 032 A2	01/03/1990	EPO			
a	EP 0 523 479 A2	01/20/1993	EPO			
a	EP 0 856 503 A1	08/05/1998	EPO			
OTHER DOCUMENTS						
a	Chow et al., <i>Poly (a,a',a'-tetrafluoro-p-xylylene)</i> , <u>Journal of Applied Polymer Science</u> , Vol. 13, No. 9, pp. 2325-2332, 1969.					
a	Chow et al., <i>The Synthesis of 1,1,2,2,9,9,10,10-octafluorou2, 2Paracyclophane</i> , <u>Journal of Organic Chemistry</u> , Vol. 35, No. 1, pp. 20-22, 1970.					
a	Iwamoto et al., <i>Crystal Structure of Poly-p-xylylene. I. The a Form</i> , <u>Jour. Polymer. Sci. Polymer. Phys. Ed.</u> , Vol. 11, pp. 2403-2411, 1973.					
EXAMINER			DATE CONSIDERED			
[Signature]			4-07-05			

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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.	
ca	3,509,075	04/28/1970	Niegish et al.				
ca	3,626,032	12/07/1971	Norris				
ca	3,694,495	09/26/1972	Norris				
ca	3,940,530	02/24/1976	Loeb et al.				
ca	4,117,308	09/26/1978	Boggs et al.				
ca	4,518,623	05/21/1985	Riley				
ca	4,823,711	04/25/1989	Kroneberger et al.				
ca	4,996,010	02/26/1991	Modrek				
ca	5,142,023	08/25/1992	Gruber et al.				
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO	
ca	GB 650 947	03/07/1951	Great Britain				
ca	GB 673 651	06/11/1952	Great Britain				
ca	WO 97/15699	05/01/1997	WIPO				
OTHER DOCUMENTS							
ca	Iwamoto et al., <i>Crystallization During Polymerization of Poly-p-xylene. III. Crystal Structure and Molecular Orientation as a Function of Temperature</i> , <u>Journal of Polymer Science Polymer. Phys. Ed.</u> , Vol. 13, pp. 1925-1938, 1975.						
ca	Lee, <i>Transport Polymerization of Gaseous Intermediates and Polymer Crystal Growth</i> , <u>J. Macromol. Sci. Rev. Macromol. Chem.</u> , C16(1), p. 79-127, 1977-78.						
ca	Sharma et al., <i>Optimizing Poly(chloro-p-Xylene) or Parylene C Synthesis</i> , <u>Journal of Applied Science</u> , Vol. 36, No. 7, pp. 1555-1565, Sept. 20, 1988.						
EXAMINER 			DATE CONSIDERED 4-7-05				

FORM PTO-1449		DOCKET NUMBER DSI 301		APPLICATION NUMBER 10/816,205		
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U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
ca	5,217,559	06/08/1993	Moslehi et al.			
ca	5,268,202	12/07/1993	You et al.			
ca	5,320,518	06/14/1994	Stilger et al.			
ca	5,475,080	12/12/1995	Gruber et al.			
ca	5,482,009	01/09/1996	Kobayashi et al.			
ca	5,538,758	07/23/1996	Beach et al.			
ca	5,572,884	11/12/1996	Christensen et al.			
ca	5,639,512	06/17/1997	Nonaka et al.			
ca	5,648,006	07/15/1997	Min et al.			
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
ca	WO 97/15951	05/01/1997	WIPO			
ca	WO 97/42356	11/13/1997	WIPO			
ca	WO 99/21705	05/06/1999	WIPO			
OTHER DOCUMENTS						
ca	Lee, <i>Polyimides, Polyquinolines and Polyquinoxalines: Tg-Structure Relationships</i> , <u>Journal of Macromolecular Science, Part C - Polymer Reviews</u> (formerly <u>Journal of Macromolecular Science, Part C - Reviews in Macromolecular Chemistry and Physics</u>) Vol. 29(4), p. 431, 1989.					
ca	Lang, <i>Vapor Deposition of Very low k Polymer Films, Poly (Naphthalene), Poly (Fluorinated Naphthalene)</i> , <u>Materials Research Society Symposium Proceedings</u> , Vol. 381, pp. 45-50, April 17, 1995.					
ca	Wary et al., <i>Polymer Developed to be Interlayer Dielectric</i> , <u>Semi-Conductor International</u> , pp. 211-216, June 1996.					
EXAMINER			DATE CONSIDERED			
			4-7-05			

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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.	
ca	5,879,808	03/09/1999	Wary et al.				
ca	5,945,170	08/31/1999	Kozak et al.				
ca	5,958,510	09/28/1999	Sivaramakrishnam				
ca	6,051,321	04/18/2000	Lee et al.				
ca	6,130,171	10/10/2000	Gomi				
ca	6,140,456	10/31/2000	Foggiator				
ca	6,144,802	11/07/2000	Kim				
ca	6,265,320	07/24/2001	Shi et al.				
ca	6,302,874	10/16/2001	Zhang				
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO	
ca	WO 99/21706	05/06/1999	WIPO				
ca	WO 99/21924	05/06/1999	WIPO				
ca	WO 99/22043	05/06/1999	WIPO				
OTHER DOCUMENTS							
ca	Wunderlick, <i>Crystal Nucleation, Growth, Annealing, Macromolecular Physics</i> , Vol. 1-2, pp. 242-243, 246-247, 1996.						
ca	Greiner, <i>Poly(1,4-xylylene)s: Polymer Films by Chemical Vapour Deposition, Trends in Polymer Science</i> , Vol. 5, No. 1, pp. 12-16, 1997.						
ca	Harrus et al., <i>Parylene Af-4: A Low ϵ_r Material Candidate for ULSI Multilevel Interconnect Applications, Material Research Society Symposium Proceedings</i> , Vol. 443, 1997.						
EXAMINER			DATE CONSIDERED				
[Signature]			4-7-05				

FORM PTO-1449		DOCKET NUMBER DSI 301		APPLICATION NUMBER 10/816,205		
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U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.
ca	6,703,462	03/09/2004	Lee			
ca	6,797,343	09/28/2004	Lee			
ca	2002/0050659	05/02/2002	Toreki et al.			
ca	2002/0120083	08/29/2002	Lee			
ca	2003/0051662	03/20/2003	Lee			
ca	2003/0072947	04/17/2003	Lee			
ca	2003/0143341	07/31/2003	Lee			
ca	2003-0188683	10/9/2003	Lee			
ca	2003-0195312	10/16/2003	Lee			
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
OTHER DOCUMENTS						
ca	Plano et al., <i>The Effect of Deposition Conditions on the Properties of Vapor-Deposited Parylene Af-4 Films</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 476, pp. 213-218, 1997.					
ca	Ryan et al., <i>Effect of Deposition and Annealing on the Thermomechanical Properties of Parylene Films</i> , <u>Material Research Society Symposium Proceedings</u> , Vol. 476, pp. 225-230, 1997.					
ca	Yang et al., <i>High Deposition Rate Parylene Films</i> , <u>Journal of Crystal Growth</u> , Vol. 183, No. 3, pp. 385-390, 1998.					
ca	Mathur et al., <i>Vapor Deposition of Parylene-F Using Hydrogen as Carrier Gas</i> , <u>Journal of Materials Research</u> , Vol. 14, No. 1, pp. 246-250, 1999.					
EXAMINER			DATE CONSIDERED			
RGC			4-7-05			

